

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Applicants : Cox *et al.*  
Serial No. : To be assigned  
Filed : Herewith  
For : A METHOD OF FORMING A DECORATIVE STRUCTURE  
AND A DECORATIVE STRUCTURE MADE BY THE  
METHOD  
Customer No. : 21003

**INFORMATION DISCLOSURE STATEMENT**

**EXPRESS MAIL NO.: ER589232466US**

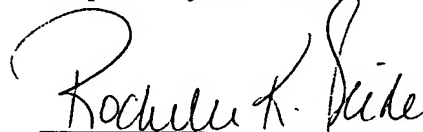
Mail Stop PATENT APPLICATION  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

Applicants bring to the Examiner's attention and enclose herewith the prior art, which are listed on the attached Form PTO 1449. Copies of the cited references are enclosed. It is respectfully requested that the listed prior art be made of record in the application.

The Commissioner is hereby authorized to charge payment of any additional fee or credit any overpayment to Deposit Account No. 02-4377.

Respectfully submitted,



Rochelle K. Seide, Ph.D.  
Patent Office Reg. No. 32,300

Dated: February 6, 2004

BAKER BOTTS L.L.P.  
30 Rockefeller Plaza  
New York, NY 10112-4498

Attorney for Applicants  
(212) 408-2500

Form PTO-1449 U.S. Department of Commerce  
(REV. 2-82) Patent and Trademark Office

Atty. Docket No.  
A36168 – 072035.0138

Serial No.  
Not Yet Assigned

**INFORMATION DISCLOSURE STATEMENT  
BY APPLICANT**  
(Use several sheets if necessary)

Applicants  
Cox et al.

Filing Date  
February 6, 2004

Group Art Unit  
Not Yet Assigned

**U.S. PATENT DOCUMENTS**

*Exam. Init.	Document No.	Date	Name	Class	Subclass	Filing Date if Appropriate
	5 7 8 3 2 6 4	07/21/98	Howes	428	13	
	4 3 4 4 9 0 6	08/17/82	Kitagawa et al.	264	128	
	3 9 6 8 0 7 3	07/06/76	Hara et al.	260	42.18	

**FOREIGN PATENT DOCUMENT**

										Class	SubClass	Translator Yes No

**OTHER DOCUMENTS (including Author, Title Date, Pertinent Pages, Etc.)**


Examiner

Date Considered

\* Examiner: Initial citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not conformance and not considered. Include copy of this form with next communication to applicant.

NY02:474580.1